

## METHOD AND APPARATUS FOR INSPECTING A SUBSTRATE

### ABSTRACT

In a method and an apparatus for inspecting defects on a substrate using a light beam,  
5 a light source irradiates light beams having different wavelengths onto the substrate. A  
detector detects first lights scattered from a surface of the substrate and second lights  
scattered from impurities on the substrate by irradiation of the light beams. An operation unit  
compares first intensities of the first lights with second intensities of the second lights in  
order to produce differential values therebetween, and selects a wavelength corresponding to  
10 a maximum value of the differential values. An inspection process for inspecting the defects  
on the substrate is performed using a light beam having the selected wavelength.